

**US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE**

**APPLICANT: MARTIN RICHARDSON
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONS**

LIST OF ART CITED BY APPLICANT

U.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AA	4,024,400	05/17/77	Blytas et al.	250	432	05/13/76
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AC	4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
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AG	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
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AI	5,148,462	09/15/92	Spitsyn et al.	378	143	04/08/91
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AK	5,243,638	09/07/93	Wang et al.	378	119	03/10/92
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OTHER ART (Including Author, Title, Date, Pertinent Pages. Etc.)

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OB T. Mochizuki, *SOFT X-RAY OPTICS AND TECHNOLOGY*, Proceedings Of SPIE-The International Society For Optical Engineering, Vol. 733, P. 23-27, December 1986

OC Martin Richardson, *LASER PLASMA SOURCE FOR X-RAY PROJECTION LITHOGRAPHY*, Laser-Induced Damage In Optical Materials, Vol. 1848, P. 483-500, 1992

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